

Special Issue

Next-Level Surface Metrology— Advances in Sensors, Data Analysis and Simulation

Message from the Guest Editors

Advancements in surface processing lead to novel and interesting problems in the research and development of processes accompanying metrology. The aim of this Special Issue is to open discussion and technical routes for further developments in this topic across the disciplines of physicists, laser engineers, data-processing experts, and system theorists. Please submit your manuscripts related, but not limited, to the following areas:

- Low-coherence interferometric metrology techniques (incl. OCT and others).
- Microscopy and coherent techniques (e.g., speckle interferometry).
- From lab to sensor (technologies for sensor fusion, autonomous calibration, and sensing as well as multi-domain sensing).
- Optical metrology-related data-processing approaches (AI, sparse data, fingerprint techniques, and others).
- Closed-loop system description, design, calibration, and/or evaluation (combination of metrology and surface processing tools) in the context of photonic surface processing and characterization.

Guest Editors

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Deadline for manuscript submissions

closed (25 January 2025)



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About the Journal

Message from the Editor-in-Chief

Metrology draws together researchers from diverse areas of metrology or measurement technology in a wide variety of applications. I encourage you to submit your manuscripts for consideration or publication in the area of measurement engineering, according to the scope of the journal. *Metrology* is supported by our authors and their institutes through low article processing charges (APC) for accepted papers. We hope you will support the journal by becoming one of our authors.

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